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Assistant Commissioner for Patents  
Washington, D.C. 20231

On June 6, 2002

TOWNSEND and TOWNSEND and CREW LLP

By Nina L. McNeill  
Nina L. McNeill

PATENT  
Attorney Docket No.: A4231/T34410  
AMAT No.  
4231/USAD01/DD/HDP/CVD/JW  
TTC Ref. No. 16301-034410US

RECEIVED  
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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of:

Michael Kwan et al.

Application No.: 09/920,891

Filed: August 2, 2001

For: GAS CHEMISTRY CYCLING TO  
ACHIEVE HIGH ASPECT RATIO  
GAPFILL WITH HDP-CVD

Examiner: Kackar, Ram N.

Art Unit: 1763

AMENDMENT

#6B  
6/18/02  
mm

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

In response to the Office Action mailed March 11, 2002 (paper no. 4),  
please amend the above-identified application as follows:

IN THE SPECIFICATION:

Please add the following section on page 1 of the application before the  
section entitled "BACKGROUND OF THE INVENTION":